

6 October 2002
Application No.:09/761,514
Docket: 1064.us

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-- This bench metrology data 330 and populated benches 131 are then passed to an alignment system 140 for a passive alignment step 250 based on the metrology data. In the preferred embodiment, this passive alignment is performed by the alignment system by plastically deforming the mounting structures 112 of the optical components 114. The alignment system 140 performs the passive alignment step 250 based upon the bench metrology data 330 and also preferably the optical component metrology data 310. By combining these two data sets, the optical axis of the individual optical elements of the optical train is aligned with respect to each other to almost the accuracy of the metrology system's data. --

Replace the paragraph beginning at page , line , in the specification as originally filed,

In the Claims:

Please amend claims 1, 7, 21, and 23-27, as follows:

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1. (amended) A micro optical train manufacturing process, comprising:
installing optical components onto an optical bench to form an optical train;
measuring positions of the optical components of the optical train; and
aligning the optical components of the optical train in response to the positions.

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7. (amended) A process as claimed in claim 6, wherein the step of aligning the optical components of the optical train is further performed in response to the determined optical property.

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21. (amended) A process as claimed in claim 1, further comprising, after aligning the optical components in response to the positions, actively aligning the optical components of the optical train.

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23. (amended) A process as claimed in claim 1, further comprising, after aligning the optical components in response to the positions, transmitting an optical signal through the optical train and further aligning the optical components of the optical train in response to the transmission of the optical signal through the optical train.